

## A Novel Protecting Group for Hindered Phenols

Marvin M. Hansen\* and Jennifer R. Riggs<sup>1</sup>

Chemical Process Research and Development Division, Lilly Research Laboratories, A Division of Eli Lilly and Company, Indianapolis, IN 46285-4813

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**Abstract**: Boc<sub>2</sub>O and DMAP were used to protect hindered phenols as their Boc derivatives under mild conditions. Deprotection conditions were developed to suppress loss of a *tert*-butyl group from the aromatic ring, or alkylation of an additional *tert*-butyl group at an unsubstituted *ortho* or *para* position. © 1998 Elsevier Science Ltd. All rights reserved.

A variety of protecting groups have been used for protection of phenols,<sup>2</sup> but few of these have been applied to hindered phenols such as di-tert-butyl phenols. Due to steric congestion, introduction and particularly removal of protecting groups on hindered phenols requires harsh conditions.<sup>3</sup> A removable protecting group was required for the substrate shown in entry 5 of the Table which would allow for subsequent metal-halogen exchange using n-butyllithium. The tert-butoxycarbonyl (Boc) group was considered since hindered carboxamides are readily protected using di-tert-butyldicarbonate (Boc<sub>2</sub>O) and 4-dimethylaminopyridine (DMAP) if they are sufficiently acidic.<sup>4</sup> We now show that the high acidity of phenols allows for the facile introduction of a Boc protecting group even for hindered phenols.<sup>5</sup> Conditions for removal of the Boc group have been discovered that avoid side reactions resulting from the liberated tert-butyl cation or from de-alkylation of the desired di-tert-butyl phenol products.

Results for the protection and deprotection of a series of phenols is provided in the Table. All substrates were commercially available except the entry 4 substrate.<sup>6</sup> Although CH<sub>2</sub>CN or CH<sub>2</sub>Cl<sub>2</sub> have been routinely used as solvents during the Boc protection of carboxamides, hexanes was found to give a cleaner product in entry 7, and this solvent was subsequently employed for all substrates. The moderately hindered phenols in entries 1-3 reacted rapidly and only a slight excess of Boc<sub>2</sub>O was required for complete conversion. The ditert-butylphenols reacted slowly and 1.2 equiv of Boc<sub>2</sub>O was necessary for complete conversion due to competition of the liberated *tert*-butyl alcohol for Boc<sub>2</sub>O. Isolated product yields were high and in some cases no purification was required.

Our initial attempt to deprotect the *O*,*N*-bis-Boc protected derivative in entry 4 was surprising. Both Boc groups were readily removed using neat trifluoroacetic acid (TFA, 60 equiv) over 1 h; however, a by-product where one of the *tert*-butyl groups from the aromatic ring was lost was isolated in 10% yield. This Friedel-Crafts-like de-alkylation<sup>7</sup> could be suppressed by using 10 equiv of TFA in CH<sub>2</sub>Cl<sub>2</sub> and carefully monitoring the reaction for completion. Under the standard conditions A in the Table, the Boc protected phenols in entries 5 and 8 were cleanly deprotected, while the phenol in entry 7 gave 4% de-alkylation. The "basicity" of the aromatic ring makes it susceptible to acid promoted de-alkylation only for the trialkyl substituted phenols.

Application of the standard TFA deprotection conditions A to substrates with unsubstituted *ortho* or *para* positions afforded a by-product where the liberated *tert*-butyl cation alkylated the aromatic ring. This alkylation product amounted to 43% of the deprotected crude product in entry 1, 5% in entry 2, 10% in entry 3 and 21% in entry 6. This side reaction was anticipated since phenol or anisole are frequently used as *tert*-butyl cation scavengers during cleavage of Boc groups.<sup>8</sup> It was hoped that this side reaction could be avoided by providing an alternate scavenger. Conditions B in the Table were developed wherein water presumably traps the *tert*-butyl cation in preference to the phenol.<sup>9</sup> These conditions afforded high yields of the corresponding phenols without any detectable alkylation products for entries 2, 3 and 6 and with only 2% of the alkylation product for entry 1.

In summary, we have developed mild conditions to protect hindered phenols as their Boc derivatives. Two potential side reactions were identified during deprotection studies: loss of a *tert*-butyl group from the phenol ring and alkylation of an additional *tert*-butyl group at an unsubstituted *ortho* or *para* position. Both side reactions were suppressed by suitable choice of reaction conditions and high yields of phenols were realized.

Table. tert-Buton	cycarbonyl Protection and	Deprotection of I	lindered Phenols
	Protection		Deprotection
Cl 1	D 4' 37' 11/07'	<b>C</b> 12.1	D 12 (1) 37

		Protect	ion	Deprotection			
Entry	Substrate	Rxn time	Yield (%)	Conditions	Rxn time (h)	Yield (%)	
1	но	5 min	98	В	3	91	
2	HO	20 min	100	В	3	85	
3	но	30 min	95	В	3	87	
4	HO S NH	3 h	89 人	A ×	5	94	
			HO′				
5	X = Br	6 h	94	' A	19	89	
6	X = H	19 h	93	В	3	89	
7	$X = CH_3$	28 h	100	Α	21	79	
8	$X = OCH_3$	41 h	83	Α	28	100	

## Representative Procedures

**Protection:** The phenol substrate and Boc<sub>2</sub>O (1.02 equiv entries 1-3, 2.2 equiv entry 4, 1.2 equiv entries 5-8) were dissolved in hexanes (0.7 M, entry 4 substrate dissolves only after an initial rapid Boc protection of the amide nitrogen<sup>4</sup>) and DMAP (0.05 equiv) was added. When the reaction was complete as judged by TLC, the mixture was partitioned between ethyl acetate, brine and 1 N HCl. The layers were separated and the organic layer was washed with aqueous NaHCO<sub>3</sub>, dried (Na<sub>2</sub>SO<sub>4</sub>) and concentrated. The products in Entries 1, 2, 5, 6 and 8 were purified by chromatography on flash silica gel. All of the Boc derivatives except for entry 6<sup>5</sup> were new compounds and had satisfactory spectral and microanalytical data.

**Deprotection Conditions A:** The substrate was dissolved in  $CH_2Cl_2$  (0.5 M) and treated with 3 equiv of TFA. When the reaction was complete as judged by TLC or HPLC, the mixture was partitioned between  $CH_2Cl_2$  and aqueous NaHCO<sub>3</sub>. The organic layer was dried (Na<sub>2</sub>SO<sub>4</sub>) and evaporated.

**Deprotection Conditions B:** The substrate was dissolved in dioxane (10 mL per g substrate) and an equivalent volume of 3 M HCl was added. The mixture was heated at reflux for 3 h, then partitioned between EtOAc and aqueous NaHCO<sub>3</sub>. The organic layer was dried (Na<sub>2</sub>SO<sub>4</sub>) and evaporated.

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<sup>&</sup>lt;sup>2</sup> Greene, T. W.; Wuts, P. G. M. *Protective Groups in Organic Synthesis*, 2nd Ed., Wiley: New York, 1991, pp. 145-174.

<sup>3</sup> Trimethylsilyl: Friedman, S.; Kaufman, M. L.; Wender, I. J. Org. Chem. 1962, 27, 664-666. MOM: Introduced under mild conditions but could not be removed under acidic conditions without decomposition of phenol. Hansen, M.M., unpublished results.

<sup>4</sup> Hansen, M. M.; Harkness, A. R.; Coffey, D. S.; Bordwell, F. G.; Zhao, Y. Tetrahedron Lett. 1995, 36, 8949-8952.

<sup>&</sup>lt;sup>5</sup> Strongly basic phase transfer conditions with Boc<sub>2</sub>O have been used to convert di-tert-butylphenol to the Boc protected derivative in 7% yield, see: Houlihan, F.; Bouchard, F.; Frechet, J. M. J.; Willson, C. G. Can. J. Chem. 1985, 63, 153-162.

<sup>&</sup>lt;sup>6</sup> Prepared as described, see: Hansen, M. M.; Harkness, A. R. Tetrahedron Lett. **1994**, 38, 6971-6974.

<sup>&</sup>lt;sup>7</sup> For de-alkylation of di-tert-butylphenols using AlCl<sub>3</sub>, see: Tashiro, M.; Fukata, G. J. Org. Chem. 1977, 42, 1208.

<sup>&</sup>lt;sup>8</sup> See ref 2 pp. 327-329.

<sup>&</sup>lt;sup>9</sup> Aqueous  $\dot{H}_2SO_4$  in dioxane eliminated *tert*-butylation of tryptophan during peptide Boc cleavage, see: Houghten, R. A.; Beckman, A.; Ostresh, J. M. *Int. J. Peptide Protein Res.* **1986**, 27, 653-658.